



Patent  
Attorney's Docket No. 027260-295

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

## In re Patent Application of

Kazuya KAMON

Application No.: 09/320,946

**Filed: May 26, 1999**

For: PHOTOMASK, FABRICATION  
METHOD OF PHOTOMASK, AND  
FABRICATION METHOD OF  
SEMICONDUCTOR INTEGRATED  
CIRCUIT

Group Art Unit: 1756

Examiner: S. Mohamedulla

PRELIMINARY AMENDMENT/STATEMENT

Assistant Commissioner for Patents  
Washington, D.C. 20231

Date: April 4, 2001

Sir:

This preliminary amendment is filed in order to facilitate processing in the above-identified application and is filed in response to the Advisory Action dated March 14, 2001 (Paper No. 8).

### REMARKS

This preliminary amendment is filed in order to respond to note no. 6 in the Advisory Action dated March 14, 2001. In particular, Applicant respectfully traverse the Examiner's statement "while *Hur* and *Lee* do not specifically teach chemical-mechanical polishing the phase shift film, it is an obvious variation of *Hur* or *Lee* to polish it as the references teach performing chemical-mechanical polishing on other areas of the mask. Applicant argues that *Hur* and *Lee* do not teach a reflection preventing film, however, they teach a light shading film". Applicant respectfully point out that a reflection preventing